



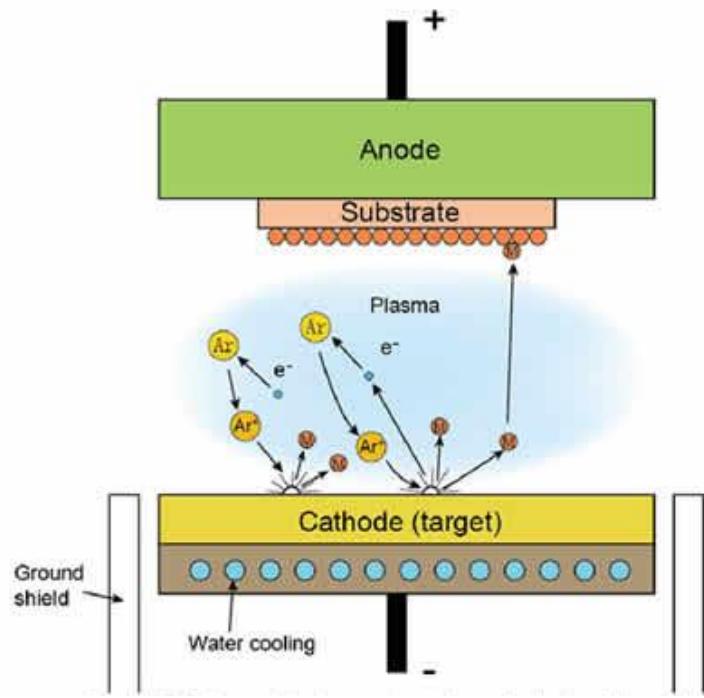
SIMULAÇÃO DA DEPOSIÇÃO DE FILMES FINOS ATRAVÉS DO PROGRAMA SIMTRA

Júlia Karnopp

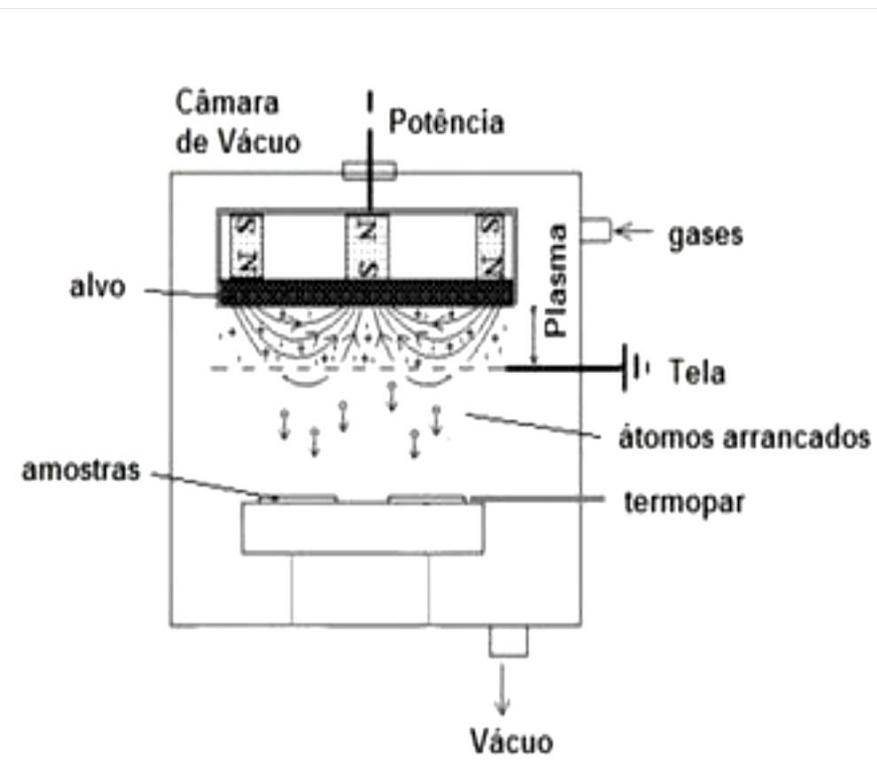
Orientador: Julio César Sagás

Deposição de filmes finos

- Magnetron sputtering
- Triodo magnetron sputtering



Sistema *magnetron sputtering*.
(<http://www.directvacuum.com/sputter.asp>)



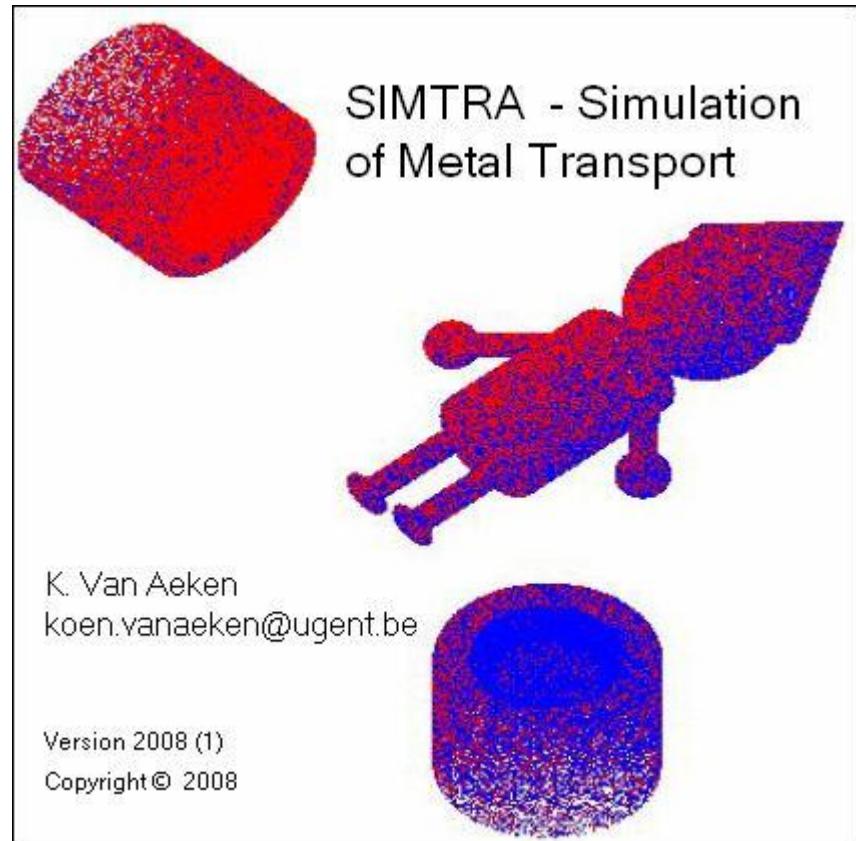
Sistema *Triodo Magnetron Sputtering* do Laboratório
de plasma da UDESC de Joinville. (Dianlen, 2013)

SIMTRA (Simulation of Metal Transport)

Utiliza o método de Monte Carlo para descrever o transporte dos átomos ejetados do alvo durante a fase de vapor.

Resultados:

- Livre caminho médio;
- Número de colisões;
- Energia;
- Cosseno do ângulo de incidência;
- Número de átomos depositados.

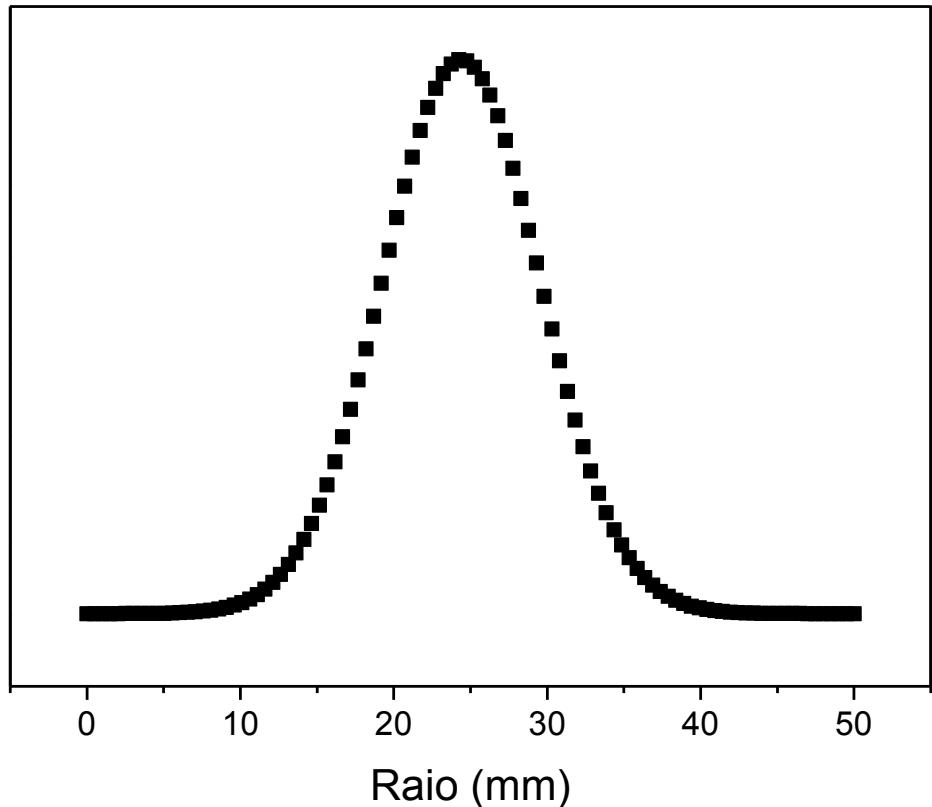


K. Van Aeken, S. Mahieu, D. Depla J. Phys. D: Appl. Phys. 41 205307 (2008)

Dados iniciais:

- Temperatura (300 K);
- Pressão;
- Gás utilizado (Ar);
- Tipo de alvo;
- Número de átomos ejetados do alvo;
- Distribuições angular e de energia dos átomos ejetados (valores calculados pelo SRIM);
- Perfil da zona de erosão do alvo;
- Geometria do reator.

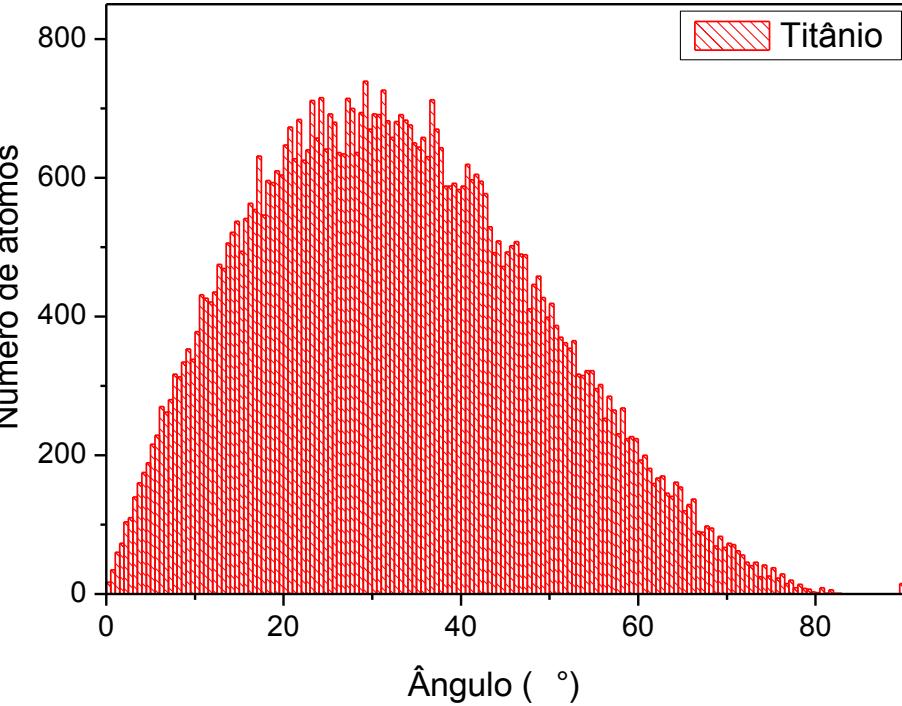
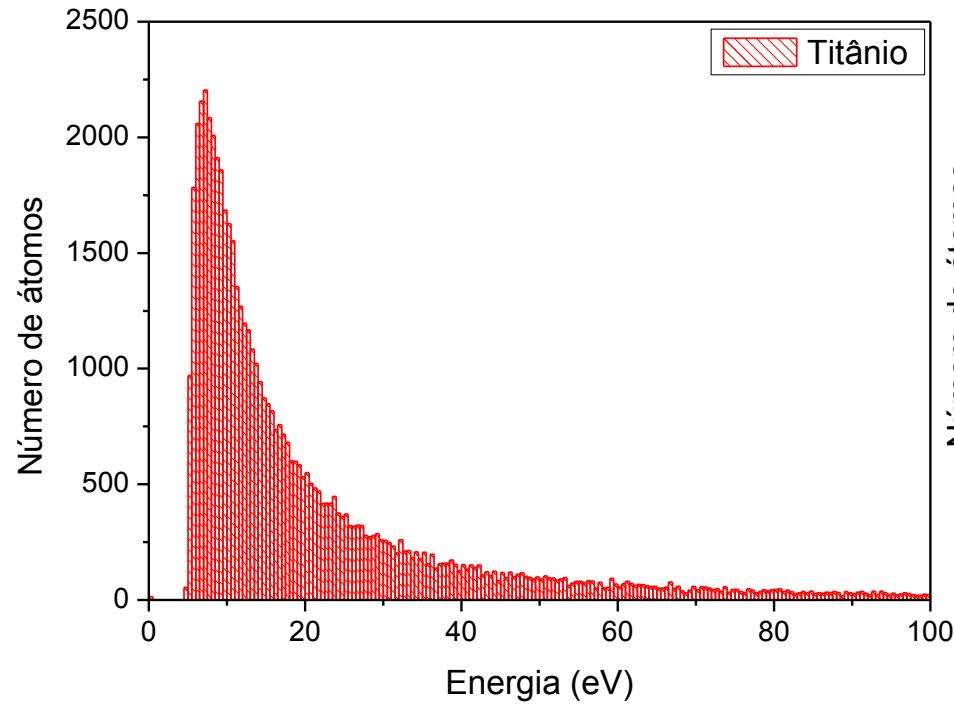
Perfil da zona de erosão:



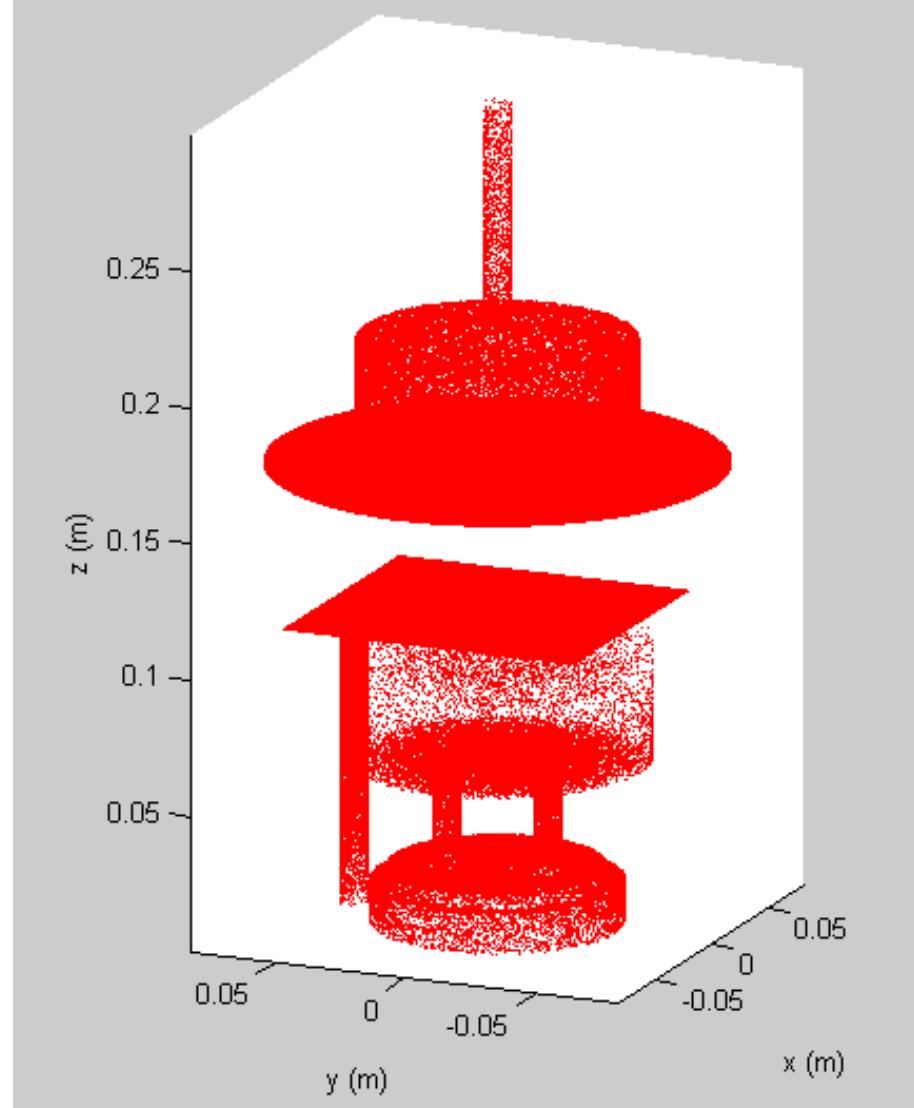
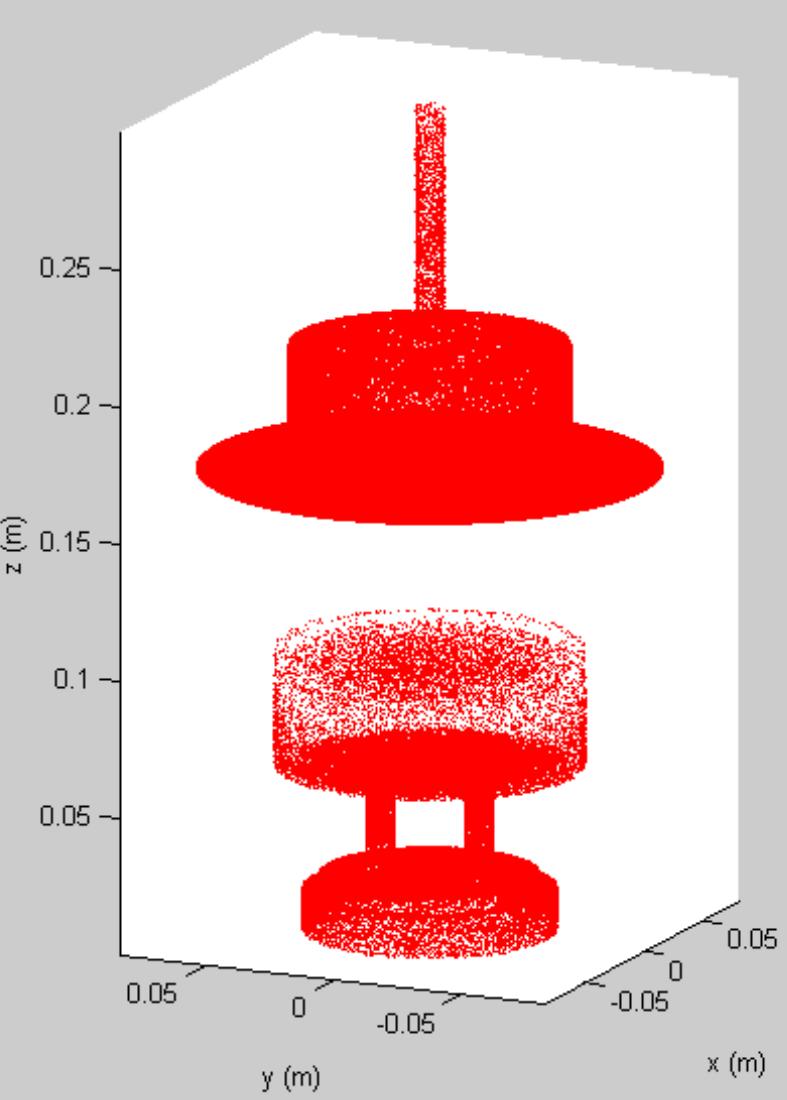
SRIM / TRIM

The Stopping and Range of Ions in Matter / Transport of Ions in Matter

- Distribuição angular e de energia dos átomos ejetados.



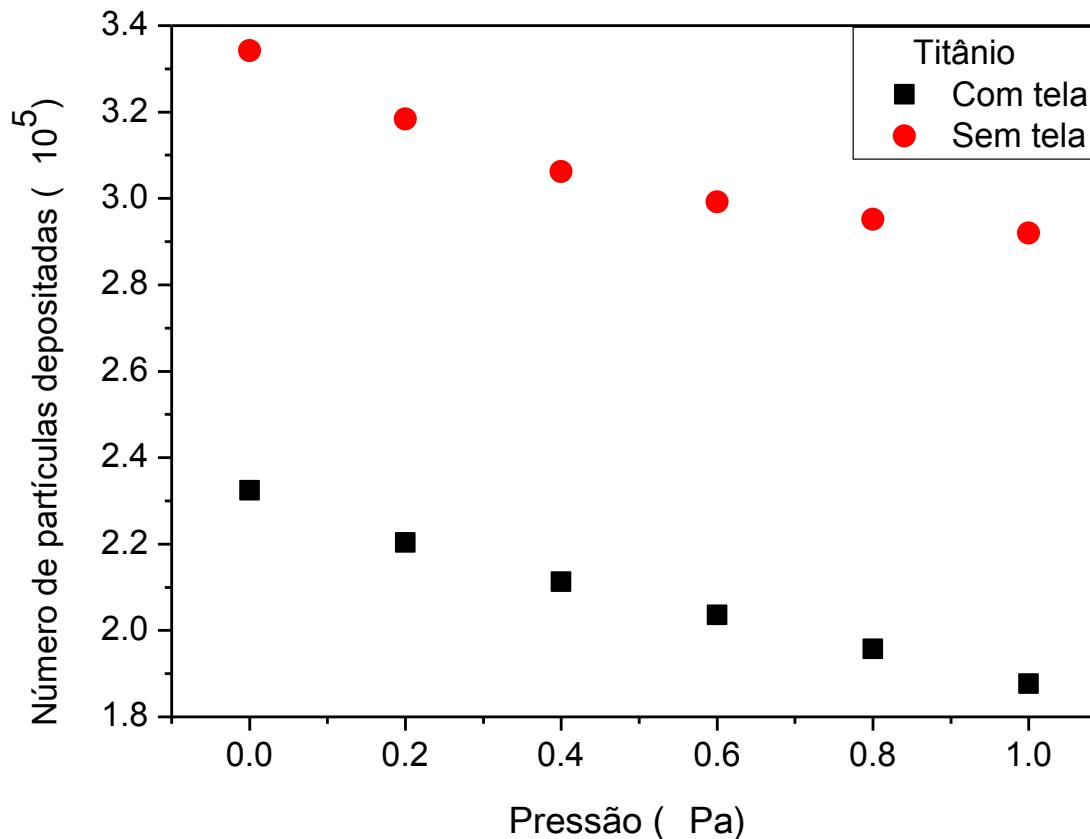
Geometria do Reator



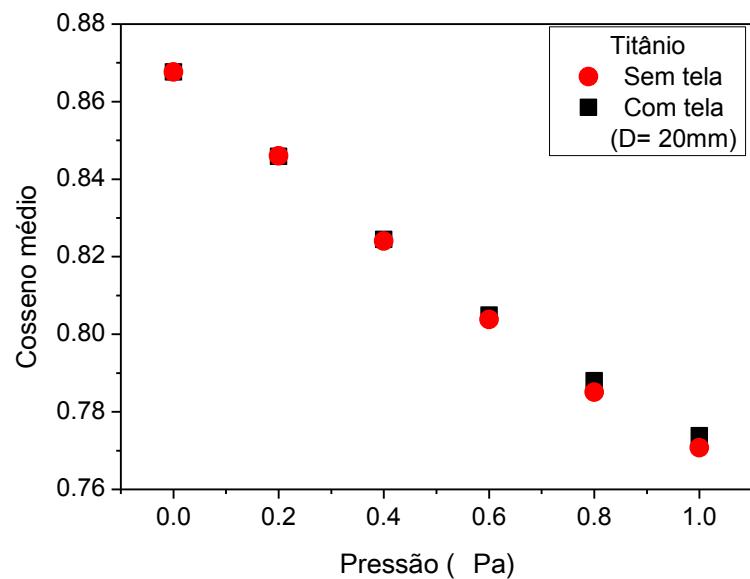
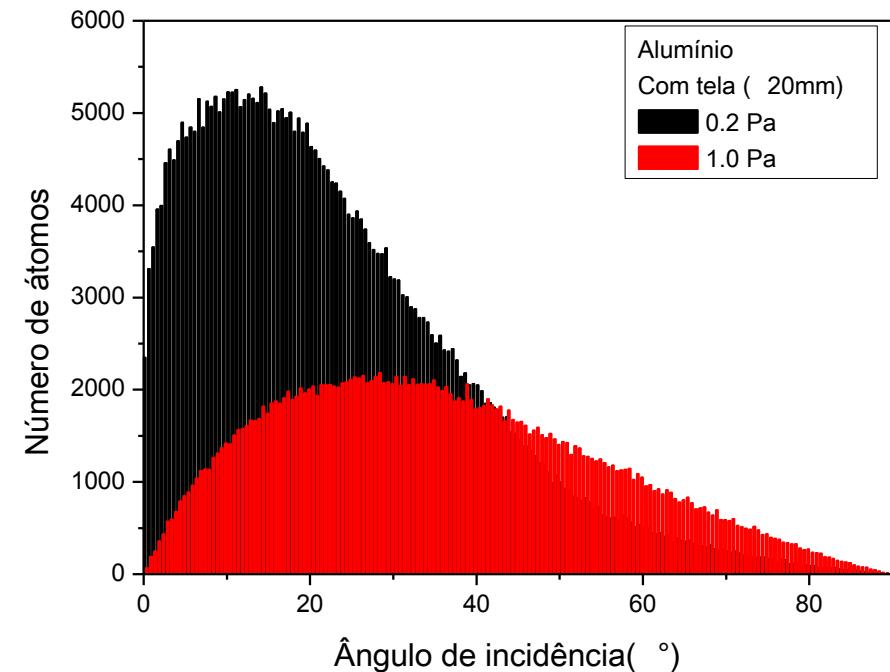
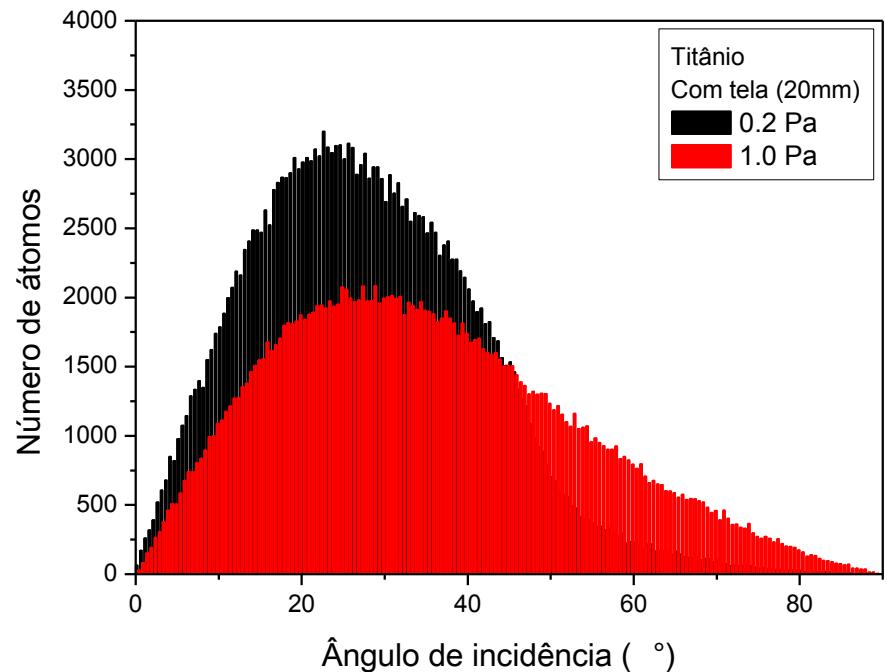
Simulações

Valores de pressão entre 0,0 e 1,0 Pa:

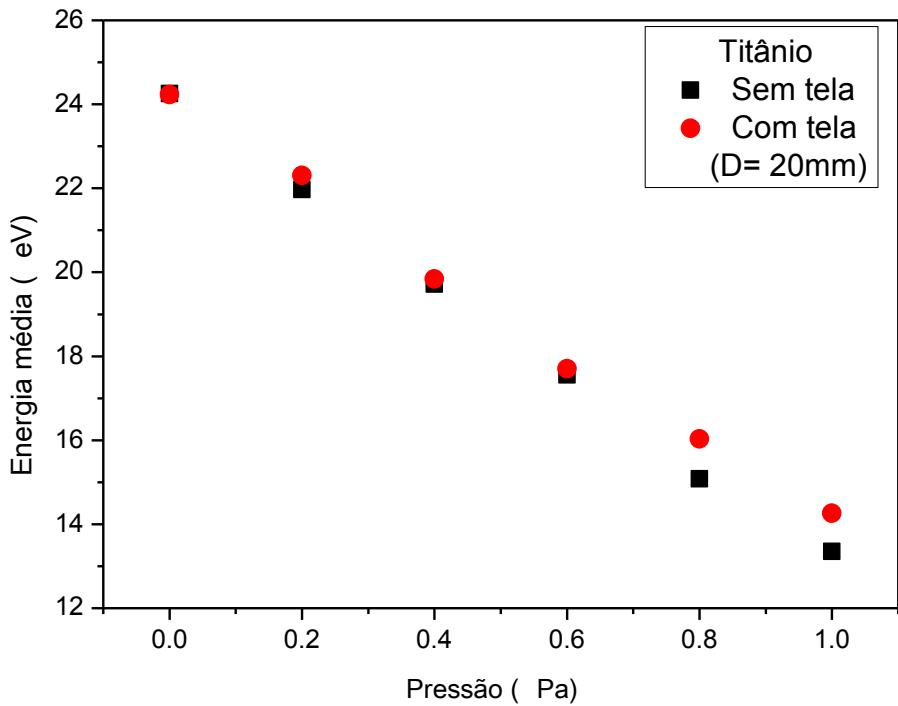
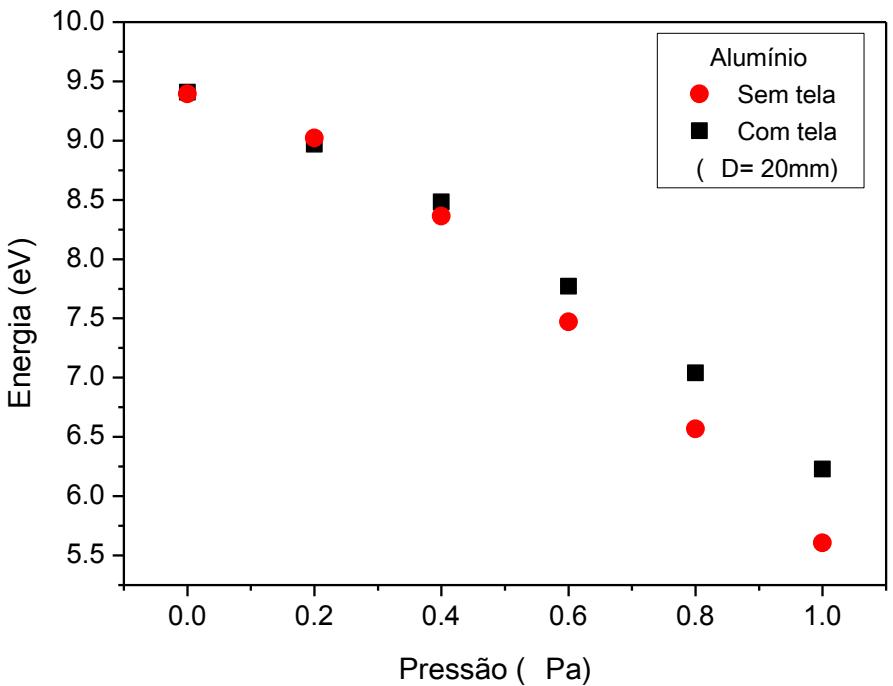
- Alvo de Titânio e Alumínio;
- Sem e com a tela a 20mm do alvo;
- 10^6 átomos ejetados.



Ângulo de incidência



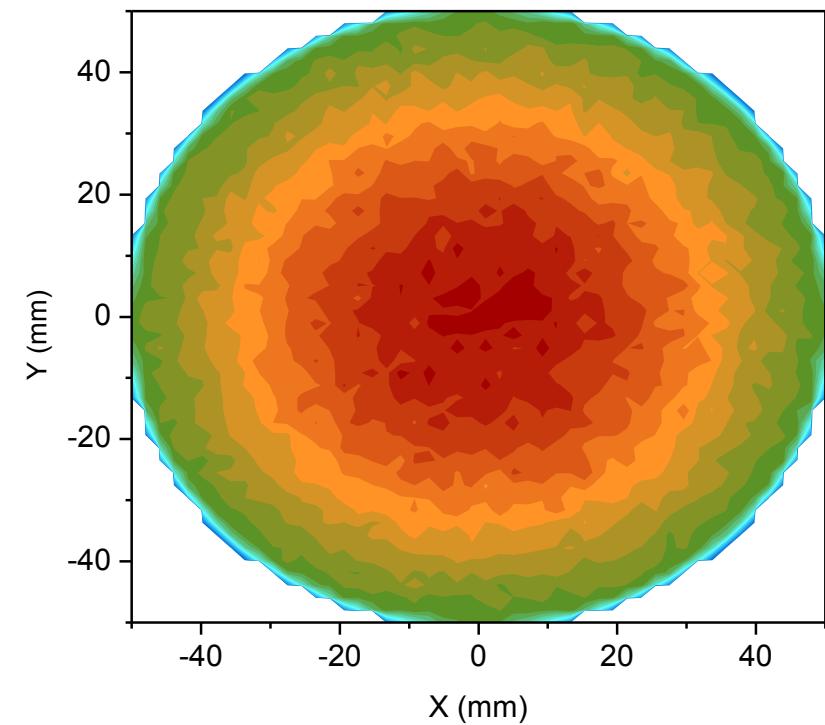
Energia



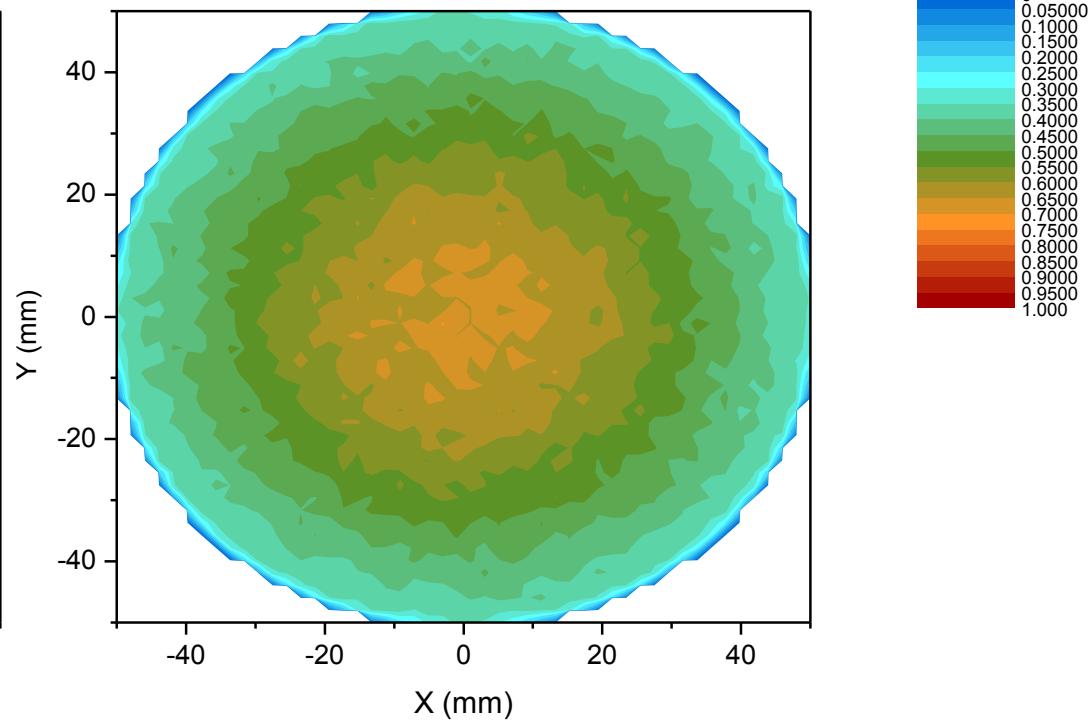
Distância da tela (10 a 40mm):

- Alvos de Titânio, Alumínio, Cobre, Gadolínio.
- Pressão: 0,4 Pa.
- 10^7 átomos ejetados.

Deposição (Titânio)

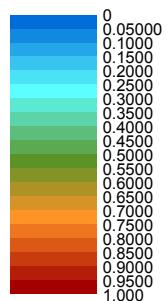
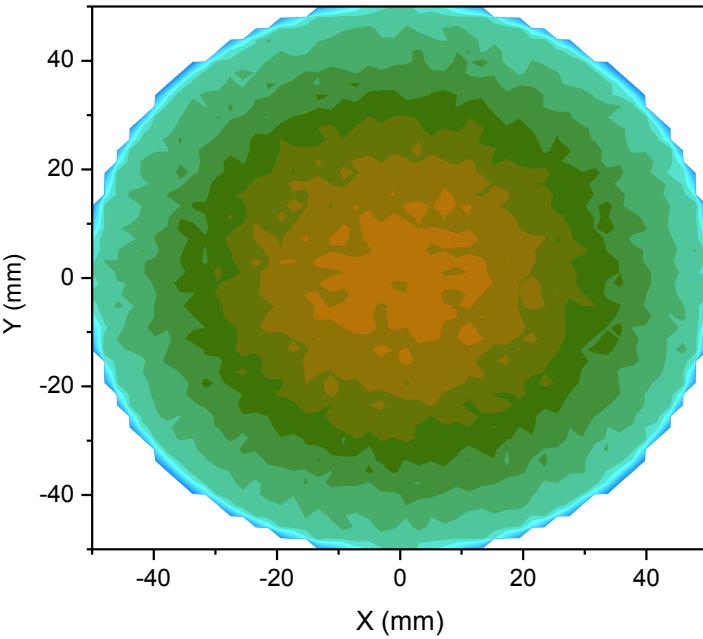
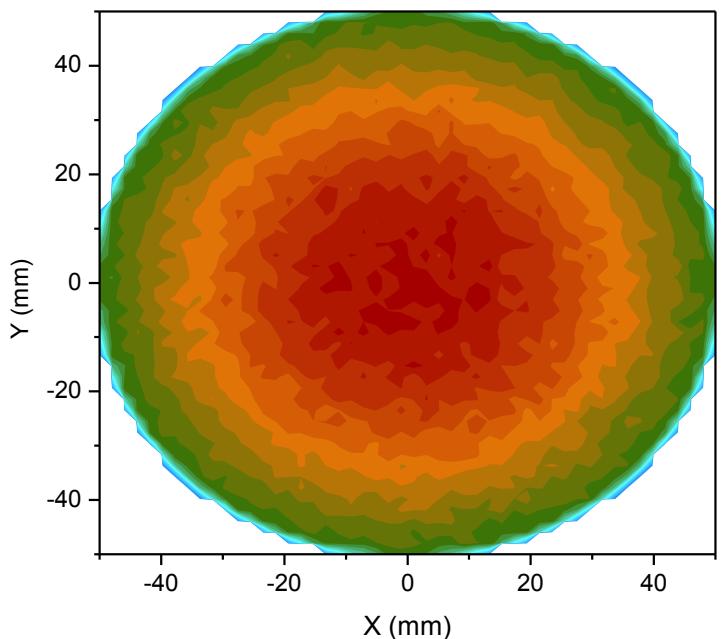


Sem tela

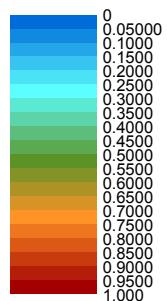
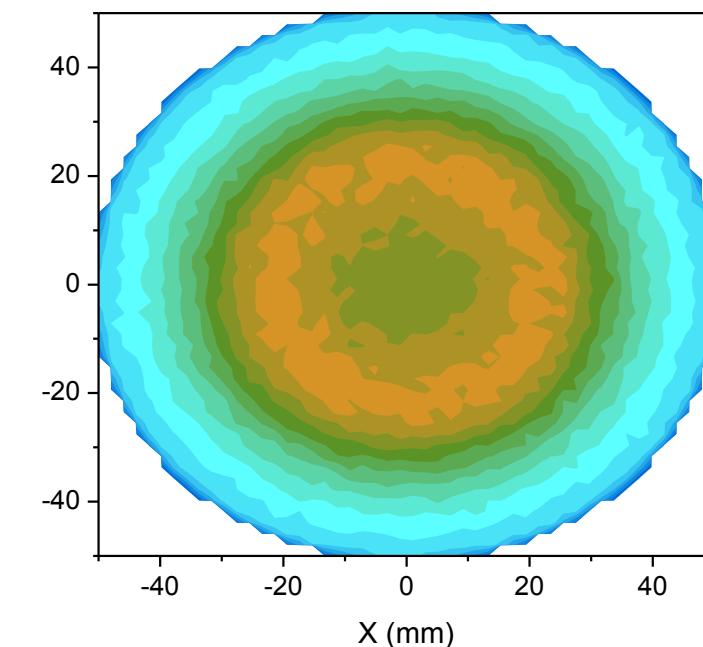
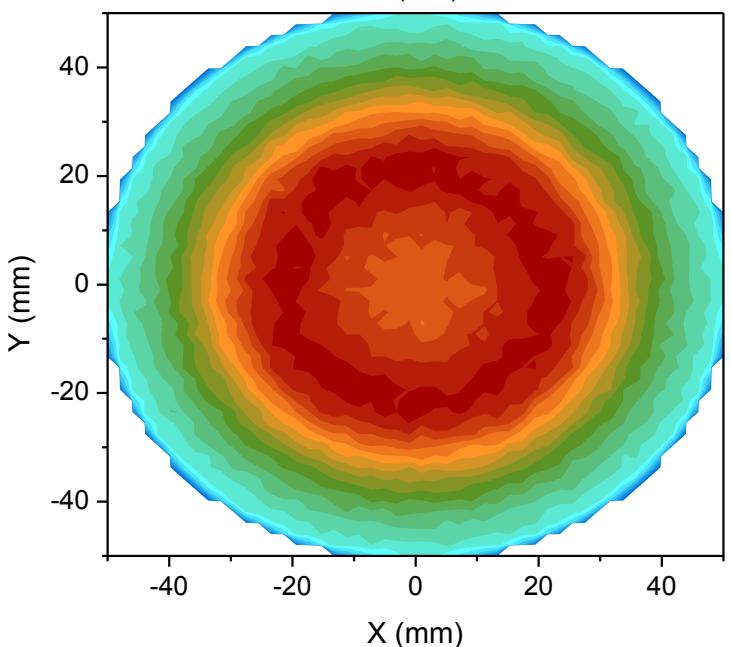


D= 20mm

Gadolínio



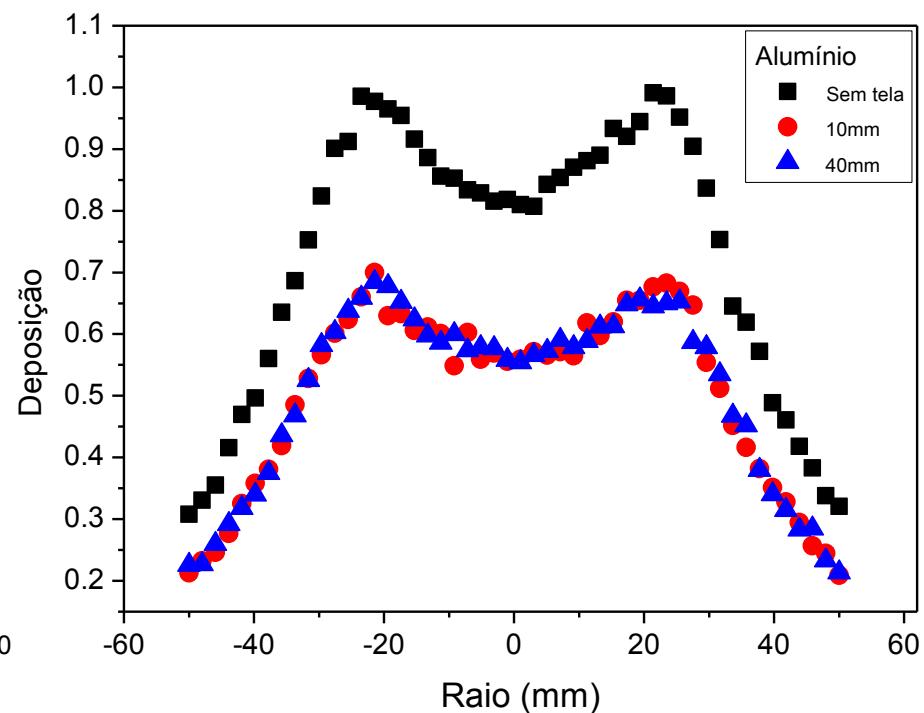
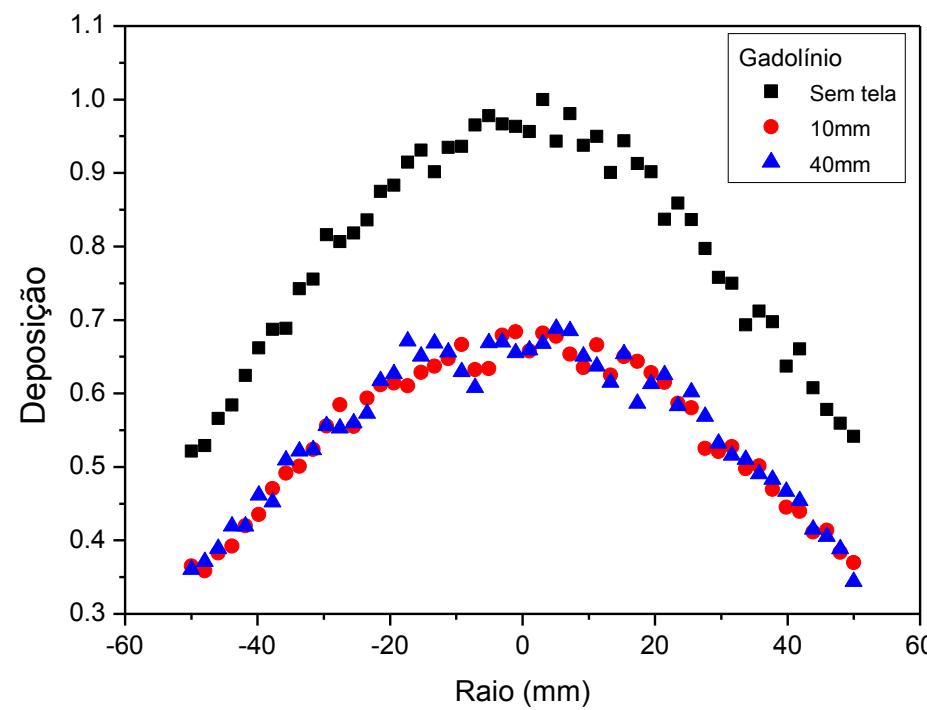
Alumínio



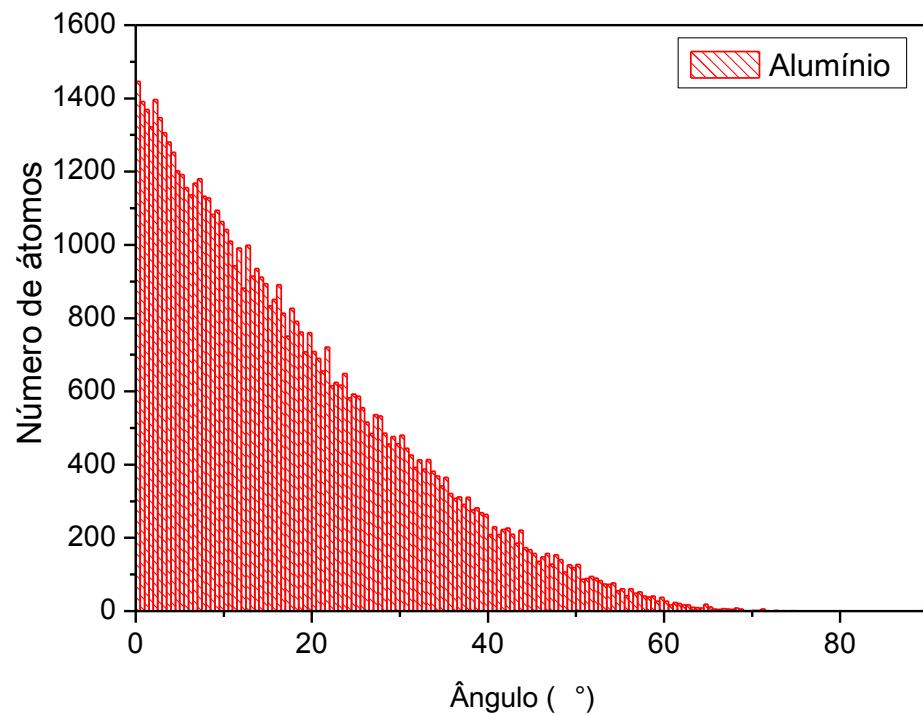
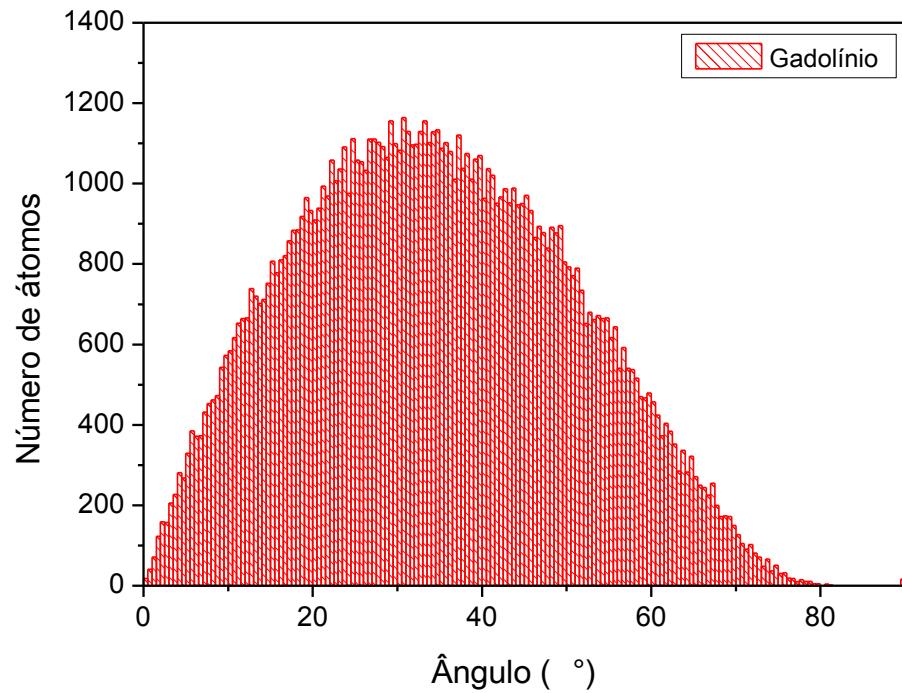
Sem tela

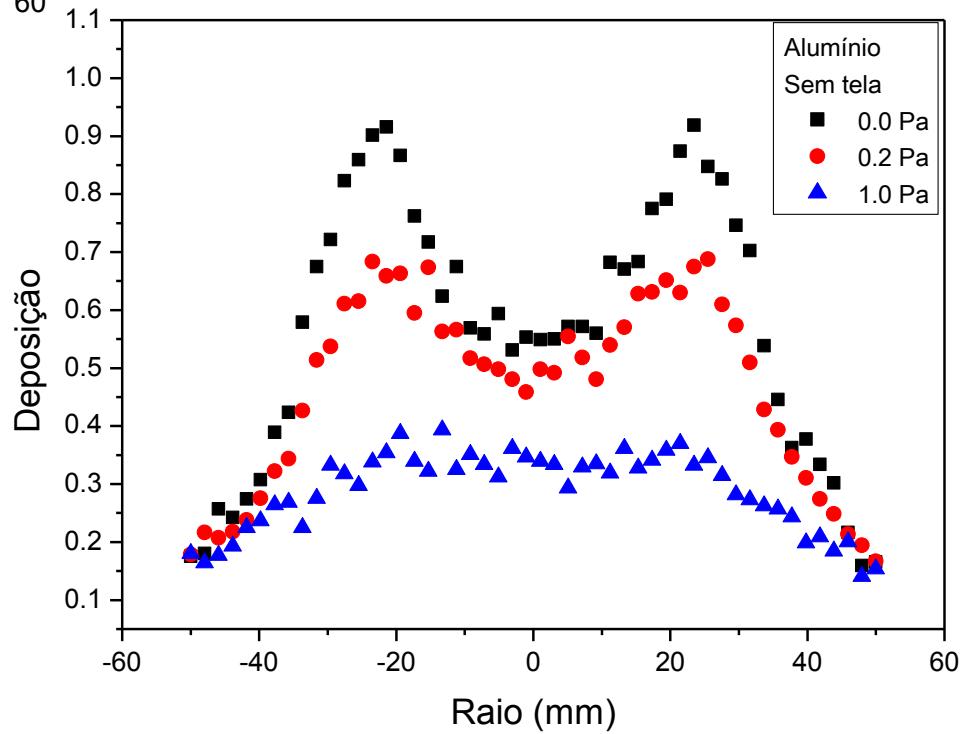
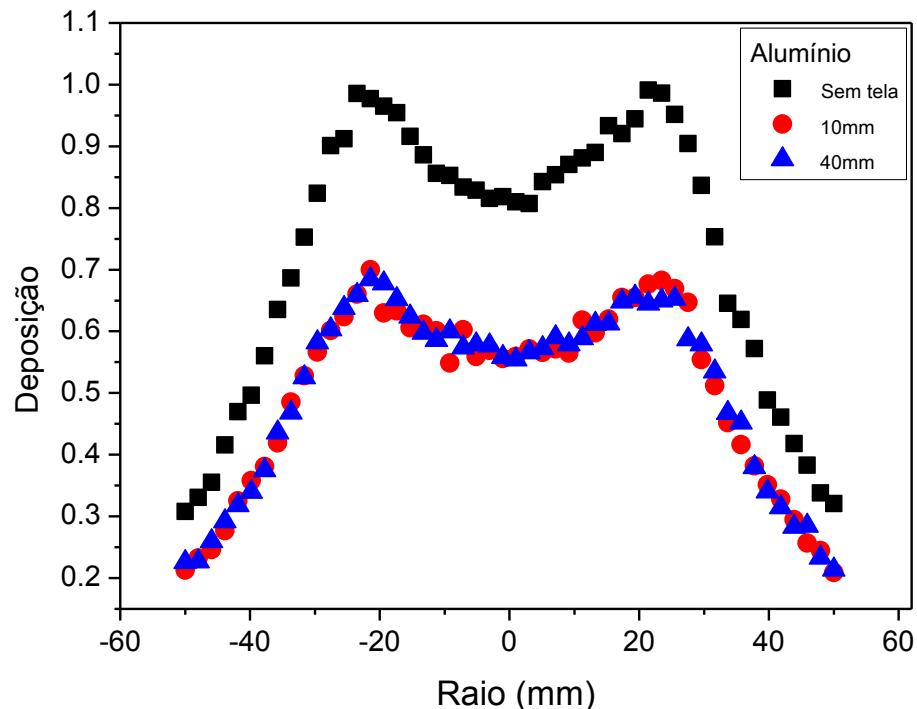
D= 20mm

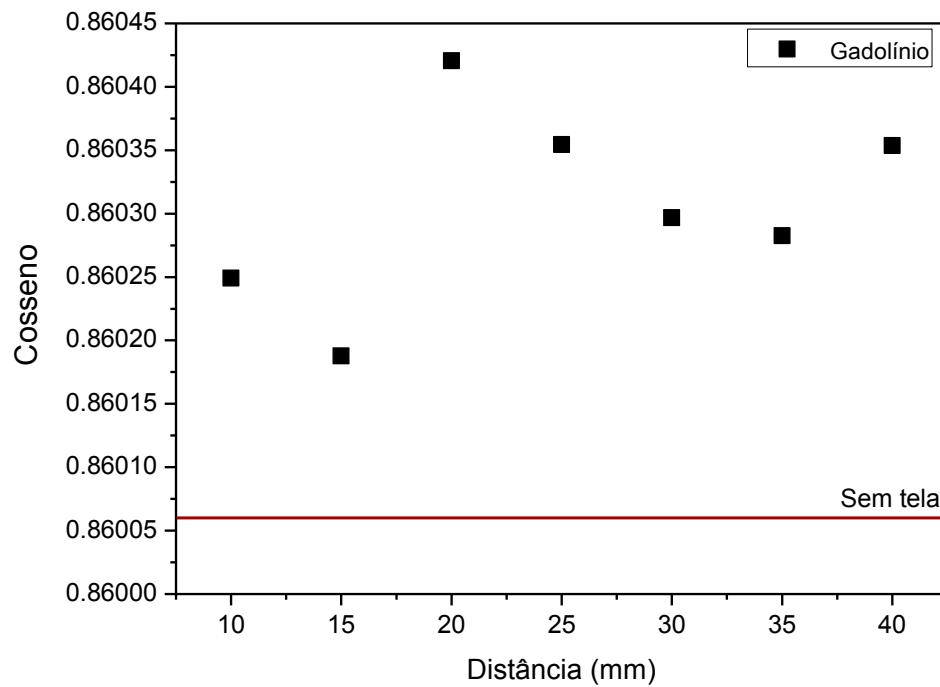
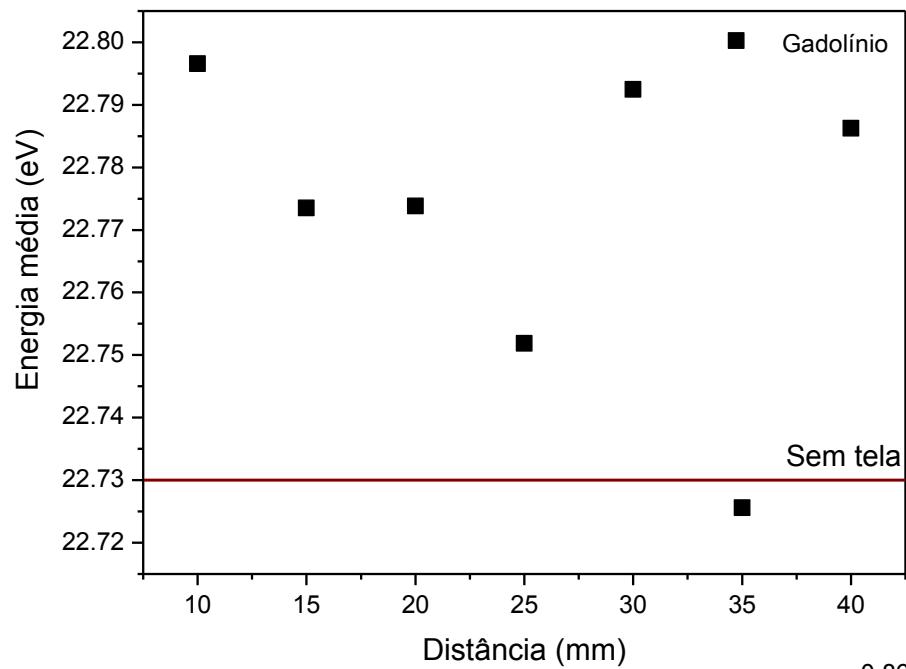
Perfil de deposição



SRIM







Conclusões

- A energia média com que os átomos se depositam diminui com o aumento da pressão.
- A distância tela-alvo não altera o valor da energia média e do ângulo de incidência dos átomos.
- A tela interfere principalmente na quantidade de átomos depositados na superfície analisada.

Referências:

- [1]** K. Van Aeken, S. Mahieu, D. Depla. Journal of Physics D.: Applied Physics 41 (2008) 20530, doi:10.1088/0022-3727/41/20/205307
- [2]** D. Depla, W.P. Leroy. Thin Solid films 520 (2012) 6337, DOI 10.1016/j.tsf.2012.06.032